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| U.S. Department of Commerce, Patent and Trademark Office | Atty Docket No. | Application No. |
| | M-10685-1C US | 09/778,245 |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | Applicant(s) | Confirmation No. |
| (Use several sheets if necessary) | Shing Lee et al. | 9085 |
| | Filing Date | Group |
| | February 6, 2001 | 2877 |

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| | | Document | Date | Country | Class | Subclass | Yes No |
| | | | | <i>none</i> | | | |
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| <i>H. J. M.</i> | | <i>3/6/03</i> | | | | | |
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